

PATENTS

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

In re application of
Attilio CITTERIO et al.
Serial No. (unknown)
Filed herewith

METHODS FOR SURFACE MODIFICATION
OF SILICA FOR USE IN CAPILLARY
ZONE ELECTROPHORESIS AND CHROMA-
TOGRAPHY

INFORMATION DISCLOSURE STATEMENT

Commissioner of Patents

Washington, D.C. 20231

Sir:

In compliance with Rules 1.97 and 1.98, and in fulfillment of the duty of disclosure under Rule 1.56, the accompanying documents, copies of which are attached to this statement, are made of record on the enclosed sheet.

A concise explanation of the relevance of these items is that we are advised by our client that these references were cited in International Application PCT/EP01/01544 filed February 13, 2001.

Respectfully submitted,

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February 27, 2002

FORM PTO-1449 U.S. DEPARTMENT OF COMMERCE PATENT AND TRADEMARK OFFICE INFORMATION DISCLOSURE STATEMENT BY APPLICANT <small>(Use several sheets if necessary)</small> (37 CFR 1.98(b))	ATTY. DOCKET NO. 2503-1005	SERIAL NO.
	APPLICANT Attilio CITTERIO et al.	
	FILING DATE February 27, 2002	GROUP

U.S. PATENT DOCUMENTS

EXAMINER INITIAL		PATENT NUMBER	ISSUE DATE	PATENTEE	CLASS	SUB CLASS	FILING DATE IF APPROPRIATE
	AA	2,417,992	3/47	Niederl			
	AB	3,366,638	1/68	Kuhnle			
	AC	4,014,678	3/77	Huppi et al.			
	AD	4,904,629	2/90	Galla et al.			
	AE	5,391,274	2/95	Shieh			
	AF						
	AG						
	AH						
	AI						
	AJ						
	AK						

FOREIGN PATENT OR PUBLISHED FOREIGN PATENT APPLICATION

		DOCUMENT NO.	PUBL. DATE	COUNTRY OR PATENT OFFICE	CLASS	SUB CLASS	TRANSLATION YES NO
	AL	836 937	4/52	Germany			no
	AM	WO 97/04308	2/97	International			yes
	AN						
	AO						
	AP						

OTHER DOCUMENTS (Including Author, Title, Date, Relevant Pages, Place of Publication)

	AR	
	AS	
	AT	

EXAMINER

DATE CONSIDERED

EXAMINER: Initial citation considered. Draw line through citation if not in conformance and not considered. Include copy of this form with next communication to applicant.